POLOS® SPIN200x SPIN COATER

The new POLOS® SPIN200x offers precise, repeatable
신형 POLOS® SPIN200x는 정밀하고 반복 가능한 공정 제어가 가능 합니다.
본 제품은 Natural 폴리프로필렌(NPP)으로 제작되 었으며,
옵션으로 PTFE 재질도 선택 가능 합니다.
기본형과 고급형 두가지 버전으로 제공됩니 다.
직경 200mm 이하의 다양한 기판 또는 150 x 150mm 크기의 사각 형 샘플 처리
에 이상적입니다.

UNIQUE DESIGN

The unique outer shell and drain design allows easy switching between table-top and in-deck model. The modular design enables the user to upgrade the unit using a wide range of different accessories to ease dispensing and overall handling.

MOTOR HOMING POSITION

The new SPINx-series has the ability to define a motor homing position, allowing for easy integration in robot controlled/automated environments.

EASY CHAMBER ACCESS

The vacuum chuck sits above the edge of the bowl allowing easy access to the wafer/substrate with an end-effector, tweezers or vacuum wand. This is a unique requirement to enable robot handling.

SPECIFICATIONS HARDWARE:

- Liquid filter trap
- Automatic lid, also controllable via foot pedal (advanced version)
- Programmable motor homing position
- Center injection holder for syringe or dispense nozzle
- Lid lock and vacuum sensor for user safety
- Large (detachable) touchscreen display
- USB-port to store recipes on USB-drive and for software updates specifications drive-unit
- Indirect brushless drive unit - up to 12.000 RPM
- High acceleration and accuracy: 1 - 30.000 RPM
- Clockwise/counter clockwise rotation and puddle mode
- Unique design to switch between desktop and in-deck model

202406-V5

AUTO LID

The lid can be automatically opened and closed using the User Interface or alternative a foot pedal (ideal for glovebox usage). In addition, it is also possible to automatically open the lid as a final step of your recipe.

LIQUID FILTER TRAP

The SPINx-series is equipped with a liquid filter trap to protect the spin coater's critical components. It will capture any liquids or resists entering the vacuum lines via the process chamber or vacuum chuck in a liquid container. The container can be viewed through a cut-out in the spinner housing, for easy maintenance.

CONFIGURATION

Process chamber Material	Natural polypropylene (NPP) or PTFE (optionally)
Max. substrate diameter	Up to 8" (200 mm) wafers Up to 6" x 6" (150 mm) substrates

SUITABLE FOR:

- Coating
- Cleaning
- Rinse/Dry
- Developing
- Etching
- PDMI and other processes

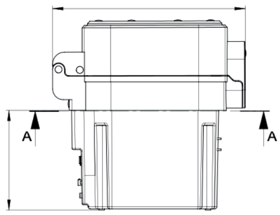
STANDARD ACCESSORIES:

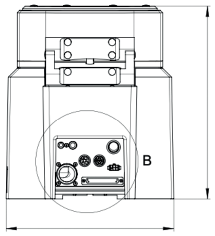
- Vacuum chuck for 4 - 8-inch wafers

STANDARD VS. ADVANCED VERSION

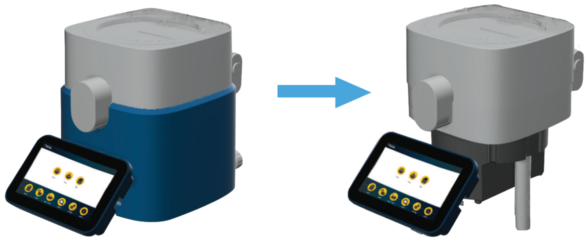
MODEL	SPIN200x STANDARD	SPIN200x ADVANCED
Liquid filter trap	Yes	Yes
Unique outer shell and drain design	Yes	Yes
Programmable motor home position	Yes	Yes
Center injection holder for syringe or dispense nozzle	Yes	Yes
Lid lock and vacuum sensor for user safety	Yes	Yes
Large (detachable) touchscreen display	Yes	Yes
USB port to store recipes on USB drive	Yes	Yes
Dispense vessel	No	Yes (optional)
Auto-closing lid	No	Yes (optional)
Linear dispense arm	No	Yes (optional)
Backside rinse	No	Yes (optional)
Available in chemical resistant PTFE	No	Yes (optional)

DIMENSIONS SPIN200x





Unique outer/inner shell and drain design allows switch between table-top and in-deck model

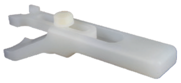


DESKTOP MODEL IN-DECK MODEL

OPTIONS

Syringe holder starter kit

Transparant 0,5 mm PET liners



Centering tool

Center dispense system: opus

Corrugated Drainhose

POLOS® Vacuum pump

POLOS® Peristaltic pump

Central dispensing syringe holder

And more. Contact us for all options!

202406-V5